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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO
09 765,148	01 17 2001	Christopher P. Ausschnitt	FIS920000191US1	7809
29505 75	06 04 2003			
DELIO & PETERSON, LLC			EXAMINER	
121 WHITNEY NEW HAVEN,			ESPLIN, DAVID B	
			ART UNIT	PAPER NUMBER
			2851	

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application No.	Applicant(s)		
		09/765,148	AUSSCHNITT, CHRIS	AUSSCHNITT, CHRISTOPHER P.	
	Office Action Summary	Examiner	Art Unit		
		D. Ben Esplin	2851		
Period fo	The MAILING DATE of this communication a or Reply	appears on the cover she	eet with the correspondence addres	ss	
THE I - Exter after - If the - If NO - Failu - Any r	ORTENED STATUTORY PERIOD FOR REF MAILING DATE OF THIS COMMUNICATION asions of time may be available under the provisions of 37 CFR SIX (6) MONTHS from the mailing date of this communication period for reply specified above is less than thirty (30) days, a period for reply is specified above, the maximum statutory perior te to reply within the set or extended period for reply will, by sta eply received by the Office later than three months after the may adequate the provided of the provision	N. 1 136(a) In no event, however, i reply within the statutory minimum od will apply and will expire SIX (6 tute, cause the application to become	may a reply be timely filed of thirty (30) days will be considered timely. b) MONTHS from the mailing date of this commit me ABANDONED (35 U S C. § 133)	unication	
1)	Responsive to communication(s) filed on _	·			
2a) <u></u>	This action is FINAL . 2b)⊠	This action is non-final.			
3) 🗌 Dispositi	Since this application is in condition for allo closed in accordance with the practice und on of Claims			nerits is	
4)	Claim(s) 1-22 is/are pending in the applicat	ion.			
	4a) Of the above claim(s) is/are withd	rawn from consideration	1.		
5)	Claim(s) is/are allowed.				
6)⊡	Claim(s) <u>1-22</u> is/are rejected.				
7)	Claim(s) is/are objected to.				
8)	Claim(s) are subject to restriction and	d/or election requiremen	t.		
Applicati	on Papers				
9) 🗌 .	The specification is objected to by the Exami	ner.			
10)	Γhe drawing(s) filed on is/are: a)□ ac	cepted or b) objected to	by the Examiner.		
	Applicant may not request that any objection to	• • •	•		
11) 🔲 -	Γhe proposed drawing correction filed on	is: a)∏ approved b	disapproved by the Examiner.		
_	If approved, corrected drawings are required in				
12) 🔲 🖰	The oath or declaration is objected to by the	Examiner.			
Priority u	inder 35 U.S.C. §§ 119 and 120				
13)	Acknowledgment is made of a claim for fore	ign priority under 35 U.S	S.C. § 119(a)-(d) or (f).		
a)[☐ All b)☐ Some * c)☐ None of:				
	1. Certified copies of the priority docume	ents have been received	l.		
	2. Certified copies of the priority docume	ents have been received	in Application No		
* S	3. Copies of the certified copies of the particular application from the International see the attached detailed Office action for a life.	Bureau (PCT Rule 17.2	(a)).	ge	
14) 🗌 A	cknowledgment is made of a claim for dome	estic priority under 35 U.	S.C. § 119(e) (to a provisional app	plication).	
	The translation of the foreign language				
Attachment					
2) Notice	e of References Cited (PTO-892) e of Draftsperson's Patent Drawing Review (PTO-948) nation Disclosure Statement(s) (PTO-1449) Paper No(s	5) Noti	rview Summary (PTO-413) Paper No(s) ce of Informal Patent Application (PTO-15 er:		
S Patent and Tr PTO-326 (Re		Action Summary	Part of Paper No 3		

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DETAILED ACTION

Claim Objections

The numbering of the claims is improper because there are two separate claims labeled as claim 8. In order to correct for this error the claims previously labeled as claims 8 (the second claim 8)-21 are hereby renumbered as claims 9-22.

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

Claims 1-22 are rejected under 35 U.S.C. 102(b) as being anticipated by U.S. Patent No. 5,965,309.

Ausschnitt teaches a process for controlling focus and dose exposure parameters in a lithographic process (see abstract) including providing a lithographic mask having a target mask portion (see col. 12 lines 44-49) containing a measurable dimension sensitive to defocus (col. 3 lines 47-49), projecting an energy beam through the target mask portion at a first focus setting in order to form a first target on a substrate (col. 3 lines 30-34), projecting an energy beam through the target mask portion onto a second location of the substrate at a second focus setting in order to lithographically form a second target (col. 4 lines 7-20), measuring the defocus sensitive dimension for each of the first and second targets and determining a desired focus setting of the

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energy beam based on the comparison of the dimensions of the first and second target (col. 3 lines 45-49). FIGS. 26a and 26b further show that the target may include first and second complementary, tone reversed target portions (complementary measurement targets 240 and 242). The first target shown includes a plurality of space element shapes of the same length and width and forming an array, and the second target shown includes an array of identical length and width, but where the first target is opaque, the second target is transparent, and vice versa. Ausschnitt also teaches that the width of the arrays (Li. Lis. Ls. Pi. and Ps) are the defocus sensitive dimension. The process discloses in Ausschnitt is used to form focus setting targets on a semiconductor wafer for use in manufacture of microelectronic circuits (see abstract).

Conclusion

The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.

- U.S. Patent No. 5,807,647 to Hashimoto discloses a process including a target portion for imaging on a substrate in order to determine an optimum focal position for the substrate.
- U.S. Patent No. 6,057,908 to Ota discloses a process including imaging a target onto a substrate at different focal positions in order to optimize focus in a lithographic manufacturing process.
- U.S. Patent No. 6,542,221 to Tang et al. discloses a process including imaging multiple targets onto a substrate in order to find the best focus position for the substrate in a lithographic process.

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Any inquiry concerning this communication or earlier communications from the examiner should be directed to D. Ben Esplin whose telephone number is (703) 305-4022. The examiner can normally be reached on Mon.-Fri. (8am-4:30 pm).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor. Russell E. Adams can be reached on (703) 308-2847. The fax phone numbers for the organization where this application or proceeding is assigned are (703) 872-9318 for regular communications and (703) 872-9319 for After Final communications.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is (703) 308-0956.

DBE

May 29, 2003

Rodney Fuller
Primary Examiner